

What Is Claimed Is:

1. A method for drying substrate ~~is a~~ method which houses substrates (1) within a processing container (3), and dries a surface of each substrate (1) by relatively lowering a fluid face of cleaning fluid (2) within a processing container (3) with respect to the substrate (1) and by introducing the drying fluid within the processing container (3), the method comprising the steps of;

Introducing drying fluid under a liquid condition within the processing container (3), and

Injecting the introduced drying fluid onto the fluid face of the cleaning fluid (2) using a nozzle (5).

2. A method for drying substrate as set forth in claim 1, further comprising the step of blowing inert gas for atomizing the drying fluid.

3. A method for drying substrate as set forth in claim 1 or claim 2, introducing drying fluid within the processing container (3) is carried out intermittently.

4. A device for drying substrate is a device which houses substrates (1) within a processing container (3), and dries a surface of

each substrate (1) by relatively lowering a fluid face of cleaning fluid (2) within a processing container (3) with respect to the substrates (1) and by introducing the drying fluid within the processing container (3), the device comprising;

Drying fluid supplying means (4) (4a) (5) for introducing drying fluid under a liquid condition within the processing container (3), and for injecting the introduced drying fluid onto the fluid face of the cleaning fluid (2) using a nozzle (5).

5. A device for drying substrate as set forth in claim 4, further comprising blowing means (6) for blowing inert gas for atomizing the drying fluid, the blowing means (6) being near the drying fluid supplying means (5).

6. A device for drying substrate as set forth in claim 4 or claim 5, further comprising control means (8) for controlling the drying fluid supplying means (4a) so as to intermittently introduce the drying fluid within the processing container (3).

7. A method for drying substrate is a method which houses substrates (1) within a processing container (3), and dries a surface of each substrate (1) by relatively lowering a

fluid face of cleaning fluid (2) within a processing container (3) with respect to the substrate (1) and by introducing the drying fluid within the processing container (3), the method comprising the steps of;

Conveying liquid drying fluid to exhaust opening (5c) of a nozzle (5) using carrier gas, and

Simultaneously blowing the drying fluid and the carrier gas from the exhaust opening (5c) towards an upper face of the cleaning fluid (2).

8. A device for drying substrate is a device which houses substrates (1) within a processing container (3), and dries a surface of each substrate (1) by relatively lowering a fluid face of cleaning fluid (2) within a processing container (3) with respect to the substrate (1) and by introducing the drying fluid within the processing container (3), the device comprising;

Drying fluid supplying means (5) (5a) (5b) (5c) for conveying liquid drying fluid to exhaust opening (5c) of a nozzle (5) using carrier gas, and for simultaneously blowing the drying fluid and the carrier gas from the exhaust opening (5c) towards an upper face of the cleaning fluid (2).

9. A device for drying substrate as set forth in claim 8, wherein the drying fluid supplying means (5) (5a) (5b) (5c) comprises a first feed pipe (5a) for supplying carrier gas to the nozzle (5) and a second feed pipe (5b) for supplying liquid drying fluid which is communicated to the halfway of the first feed pipe (5a).
10. A device for drying substrate as set forth in claim 8, wherein the drying fluid supplying means (5) (5a) (5b) (5c) comprises a first feed pipe (5a) for supplying carrier gas to the nozzle (5) and a second feed pipe (5b) for supplying liquid drying fluid to the nozzle (5), the first feed pipe (5a) and the second feed pipe (5b) being independently provided from one another.